REMARKS/ARGUMENTS

Favorable reconsideration of this application in light of the following discussion is respectfully requested.

Claims 1 and 3-6 are now active in this application. Claims 7 and 8 have been withdrawn, and claim 2 has been canceled. Claim 1 is herein amended. Support for the amendment of claim 1 is found at least in the specification at page 12, lines 7-15; at page 13, line 13 to page 14, line 8; at page 15, line 11 to page 16, line 3; and at Figure 1. No new matter is added.

In the outstanding Office Action, Claims 1, 3, and 4 were rejected under 35 U.S.C. §103(a) as obvious over Ito, EP 1146569, in view of De Francesco, U.S. Patent No. 5,733,511. Claim 5 was rejected under 35 U.S.C. §103(a) as obvious over Ito and De Francesco in view of Pote, U.S. Patent No. 5,239,134. Claim 6 was rejected under 35 U.S.C. §112, second paragraph. Claim 6 was objected to for informalities.

Applicants submitted a response on May 11, 2009. The rejections under 35 U.S.C. §112, second paragraph and the objections to formalities were obviated by that response, but the remaining rejections were maintained, as indicated in the Advisory Action of May 20, 2009.

Claims 1, 3, and 4 were rejected under 35 U.S.C. §103(a) as obvious over Ito in view of De Francesco. Claim 5 was rejected under 35 U.S.C. §103(a) as obvious over Ito and De Francesco in view of Pote, U.S. Patent No. 5,239,134. Claim 1, from which claims 3-6 depend, is amended. Applicants submit that these rejections are obviated by the present amendment of claim 1.

Amended claim 1 is directed to a method for plasma-enhanced chemical vapor deposition in which a discharge electrode and a substrate are disposed opposite to each other

in a vacuum film formation chamber. A gas for forming a film containing a substance has been introduced into the vacuum film formation chamber. High-frequency electric power generated by a high-frequency electric power feeding circuit is fed to a plurality of feeding points provided to the discharge electrode through a plurality of external cables which are disposed outside the vacuum film formation chamber. The electric power is then fed through a plurality of internal cables which are disposed inside the vacuum film formation chamber. The internal cables correspond with the external cables, respectively, so as to generate plasma between the discharge electrode and the substrate to vapor deposit the substance on the substrate. The discharge electrode is assembled from a plurality of longitudinal electrodes which are parallel, with a pair of transverse electrodes disposed in parallel and opposite to the longitudinal electrode. Each of the transverse electrodes is provided with a plurality of feeding points. A plurality of high-frequency electric power supplies feed the high-frequency electric power to the plurality of the feeding points through the external cable and the internal cables. Phases of the high-frequency electric power at the feeding points are adjusted by changing electrical characteristics of the external cables. The high-frequency electric power is fed to the plurality of feeding. The phases of the high-frequency electric power at the feeding points are adjusted by (1) carrying out vapor deposition with change in electrical characteristics of the external cables, (2) carrying out observations of the condition of the substance which has been vapor deposited on the substrate, and (3) changing the electrical characteristics of the external cables on the basis of the observations.

The Office asserts in the outstanding Office Action that the combination of Ito, De Francesco, and/or Pote render the claims obvious. However, every word in a claim must be considered in determining the question of patentability against the prior art. *In re Wilson*, 424 F.2d 1382, 1385 (CCPA 1970). Neither of the recited references teach or suggest the present method, in which the discharge electrode is assembled from a plurality of longitudinal

electrodes which are parallel, and a pair of transverse electrodes are disposed in parallel and opposite to the longitudinal electrode, with each of the transverse electrodes being provided with the plurality of feeding points. Nor do the cited references teach that a plurality of high-frequency electric power supplies feed the high-frequency electric power to the plurality of the feeding points through the external cable and the internal cables. Failing to teach or suggest these elements, Applicants respectfully request withdrawal of the present rejections, and allowance of claim 1 and the claims depending therefrom.

In light of the above discussion, the present application is believed to be in condition for allowance. An early and favorable action to that effect is respectfully requested.

Respectfully submitted,

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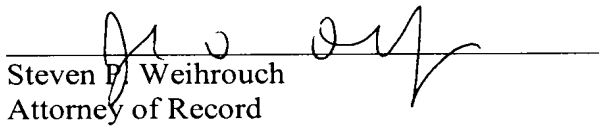

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